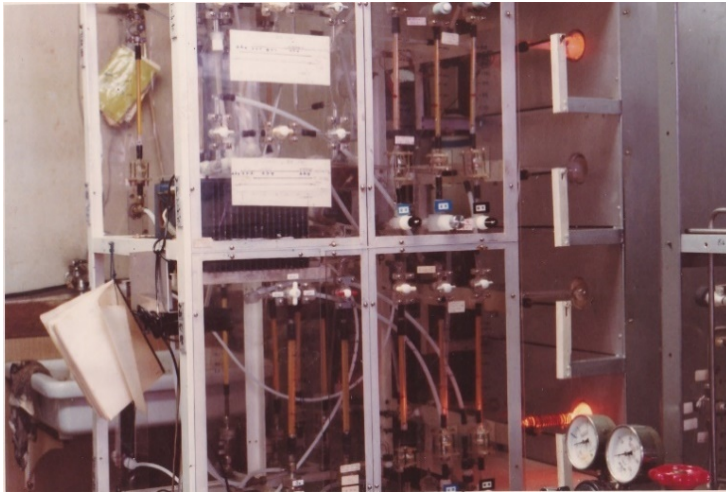
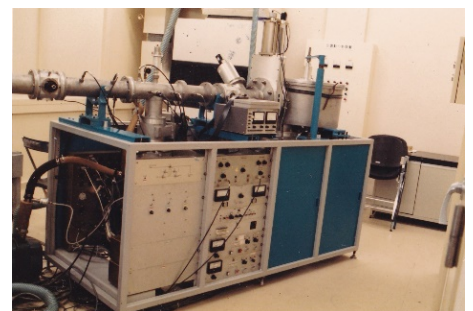
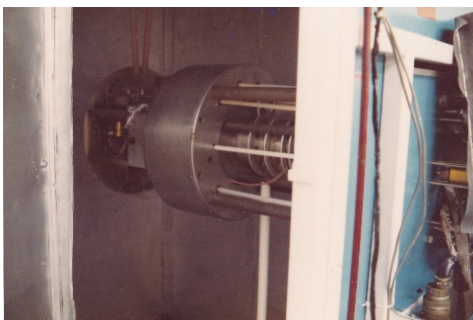
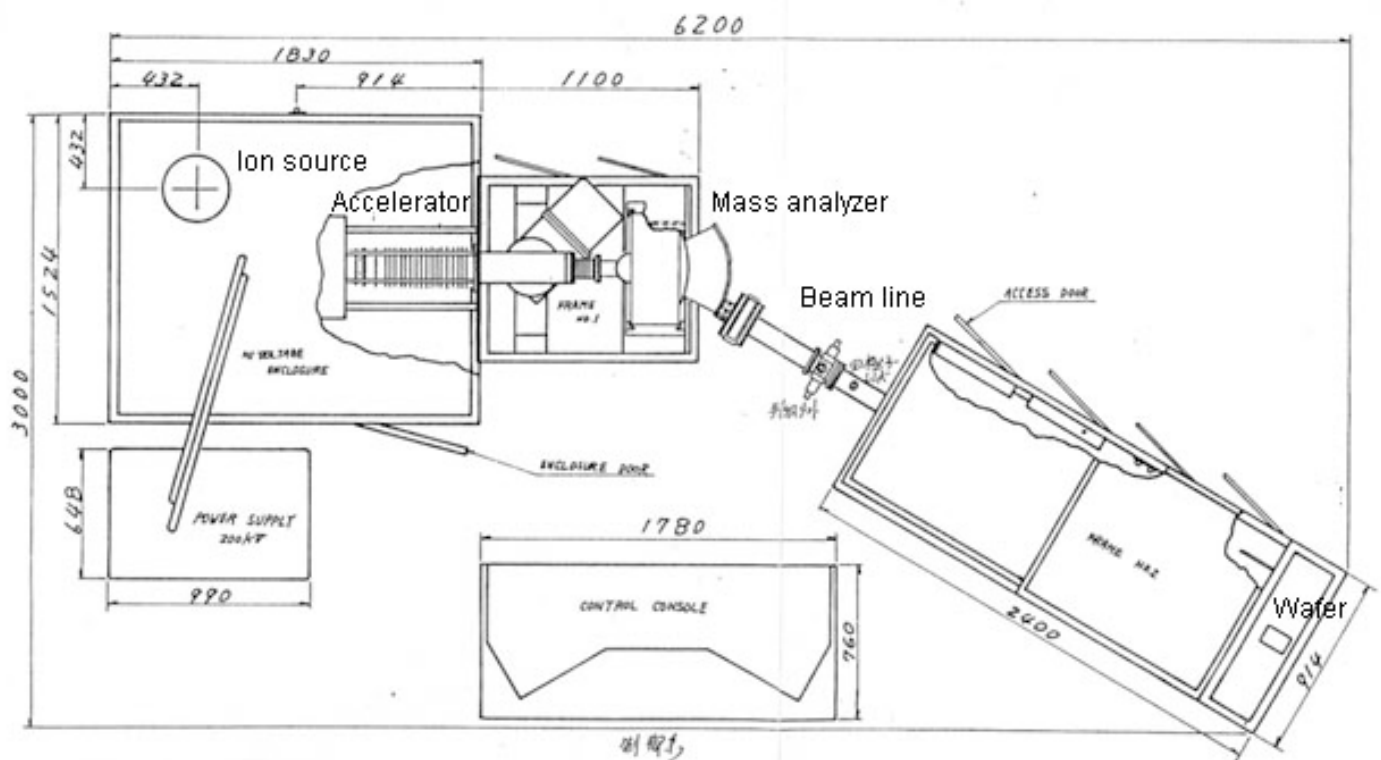


3 Wafer process (oxidation, diffusion, ion implantation)



Oxidation diffusion furnace (Liquid source BCl_3 , POCl_3)

Glass pipe line (exhibited)



Ion implanter (Accelerator Corp. 200kV)